

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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| Applicant : | Vernon et al. | Art Unit : | Unknown |
| Serial No. : | | Examiner : | Unknown |
| Filed : | March 26, 2004 | Assignee : | Intel Corporation |
| Title : | CONTINUOUS SLOPED PHASE EDGE ARCHITECTURE FABRICATION TECHNIQUE USING ELECTRON OR OPTICAL BEAM BLUR FOR SINGLE PHASE SHIFT MASK RET | | |

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Applicants submit the references listed on the attached form PTO-1449.

This statement is being filed with the application. A copy of the listed U.S. document is not provided in accordance with the waiver posted on the U.S. Patent Office website. Accordingly, only copies of non-patent literature are enclosed.

Consideration of the foregoing and enclosures plus the return of a copy of the enclosed form PTO-1449 with the Examiner's initials in the left column per MPEP 609 are earnestly solicited along with an early action on the merits.

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Date: March 26, 2004

Respectfully submitted,

Kempan Ruch

Scott C Harris
Reg. No. 32,030

/BY
KENYON S. JENCKES
REG. NO. 41,873

Attorneys for Intel Corporation
PTO Customer No. 20985
 Fish & Richardson P.C.
 12390 El Camino Real
 San Diego, California 92130
 Telephone: (858) 678-5070
 Facsimile: (858) 678-5099

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| Substitute Form PTO-1449 (Modified) | U.S. Department of Commerce Patent and Trademark Office | Attorney's Docket No. 10559-920001 | Application No. |
| Information Disclosure Statement by Applicant (Use several sheets if necessary) (37 CFR §1.98(b)) | | Applicant Vernon et al. | |
| | | Filing Date March 26, 2004 | Group Art Unit |

| U.S. Patent Documents | | | | | | | |
|-----------------------|-----------|-----------------|------------------|-------------|-------|----------|----------------------------|
| Examiner Initial | Desig. ID | Document Number | Publication Date | Patentee | Class | Subclass | Filing Date If Appropriate |
| | AA | 6,436,590 B2 | 8/20/2002 | Wang et al. | | | |
| | AB | | | | | | |
| | AC | | | | | | |
| | AD | | | | | | |
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| Foreign Patent Documents or Published Foreign Patent Applications | | | | | | | | |
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| Examiner Initial | Desig. ID | Document Number | Publication Date | Country or Patent Office | Class | Subclass | Translation | |
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| | AL | | | | | | | |
| | AM | | | | | | | |
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| | AP | | | | | | | |

| Other Documents (include Author, Title, Date, and Place of Publication) | | |
|---|-----------|---|
| Examiner Initial | Desig. ID | Document |
| | AQ | Wang et al., "Polarized Phase Shift Mask: Concept, Design, and Potential Advantages to Photolithography Process and Physical Design", Proceedings of the SPIE; The International Society for Optical Engineering Conference; vol. 4562; pgs. 406-417, 2002. |
| | AR | Pfau et al., "Gradient Phase-Shifter Transitions Fabricated by Ion Milling", SPIE, Vol. 1674 Optical/Laser Microlithography V, pgs. 585-593, 1992. |
| | AS | |
| | AT | |

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| Examiner Signature | Date Considered |
| EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. | |